

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

PRIORITY Application Serial No.10/323,525
PRIORITY Filing DateDecember 18, 2002
Inventor Alan R. Reinberg
AssigneeMicron Technology, Inc.
PRIORITY Group Art Unit 2824
PRIORITY Examiner Christian D. Wilson
Attorney's Docket No. MI22-2491
Title: Microelectronic Device Fabricating Methods, and Methods of Forming
a Pair of Field Effect Transistor Gate Lines of Different Base Widths
From a Common Deposited Conductive Layer

PRELIMINARY AMENDMENT

To: Mail Stop Patent Application
Commissioner for Patents
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VIA EXPRESS MAIL

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Please enter the following amendments prior to examining the above-identified application.

AMENDMENTS